

## ABSTRACT OF THE DISCLOSURE

A liquid processing apparatus comprises a substrate rotating device including a holder for holding a substrate and a rotating device for rotating the holder, a posture changing mechanism for changing the posture of the substrate rotating device such that a state of the substrate held by the holder changes between substantially vertical and a substantially horizontal, a process chamber for applying the liquid processing to the substrate held substantially vertical by the holder, and a position adjusting mechanism for relatively adjusting the positions of the process chamber and the holder such that the holder is housed in the process chamber. The substrates are taken out of the container hosing the substrates in a substantially horizontal state and are allowed to be held by the holder. The posture of the holder holding the substrates is changed to allow the substrates to assume a substantially vertical posture, and a predetermined process liquid is supplied to the substrates while rotating the substrates so as to carry out the liquid processing.